

1A

7: LDD REGION

9: GATE ELECTRODE

10: SIDEWALL

8: GATE DIELECTRIC FILM

2: ELEMENT ISOLATION DIELECTRIC FILM

1: SEMICONDUCTOR SUBSTRATE

5: FIRST IMPURITY DIFFUSION REGION

6: SECOND IMPURITY DIFFUSION REGION

IMPURITY CONCENTRATION

6: SECOND IMPURITY DIFFUSION REGION

4: SOURCE/DRAIN REGION

5: FIRST IMPURITY DIFFUSION REGION

4: SOURCE/DRAIN REGION

6: SECOND IMPURITY DIFFUSION REGION

DEPTH FROM THE SUBSTRATE SURFACE

FIG. 2A

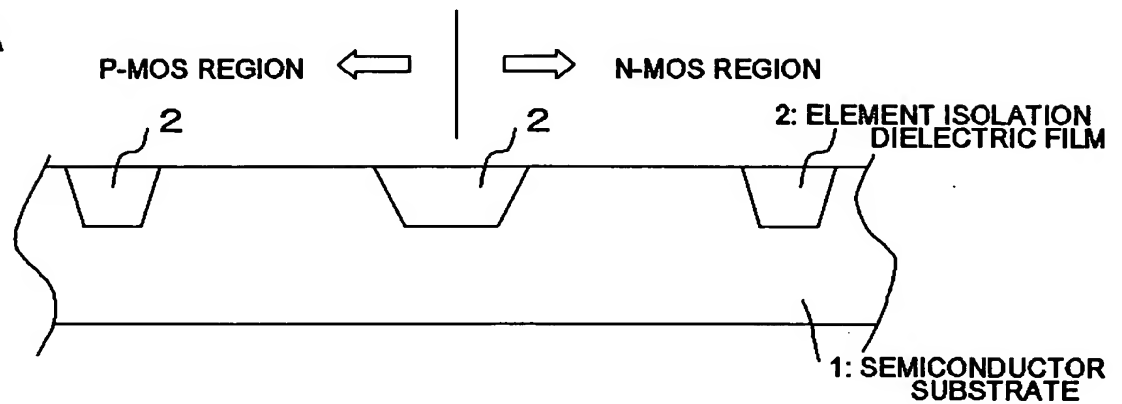


FIG. 2B

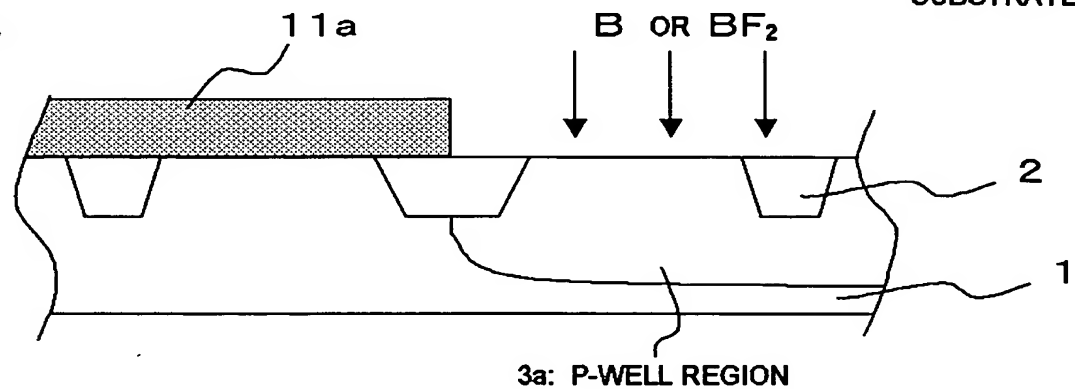


FIG. 2C

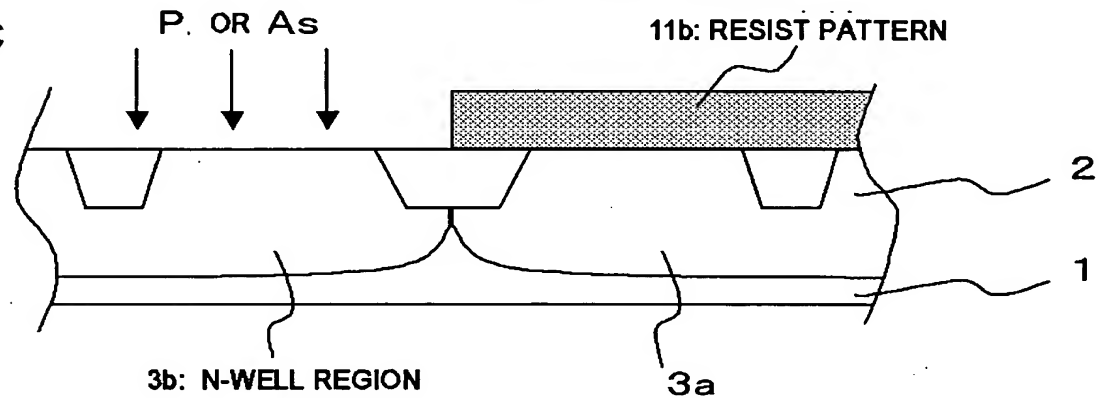


FIG. 2D

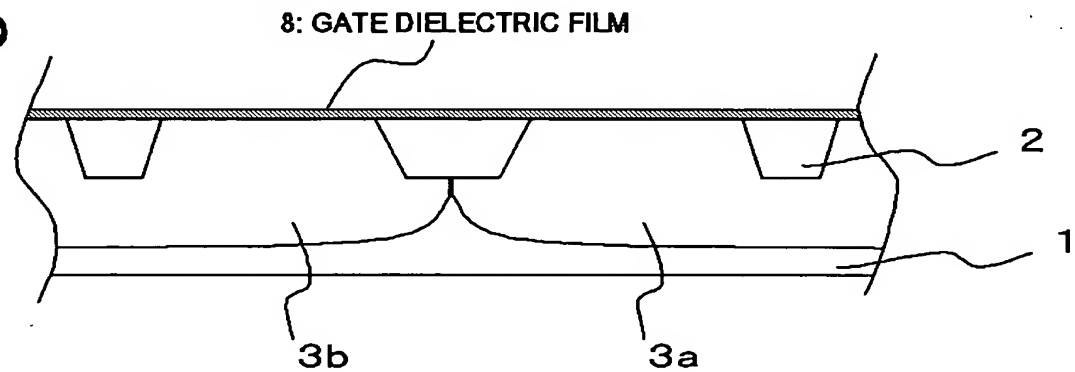


FIG. 3A

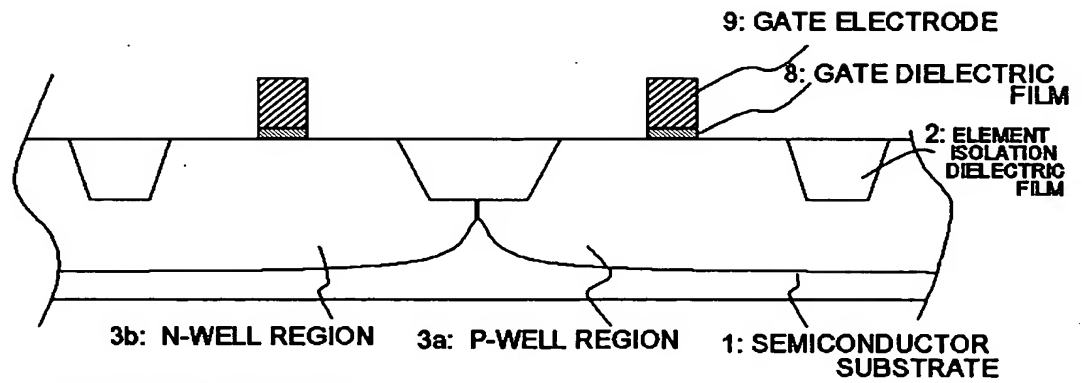


FIG. 3B

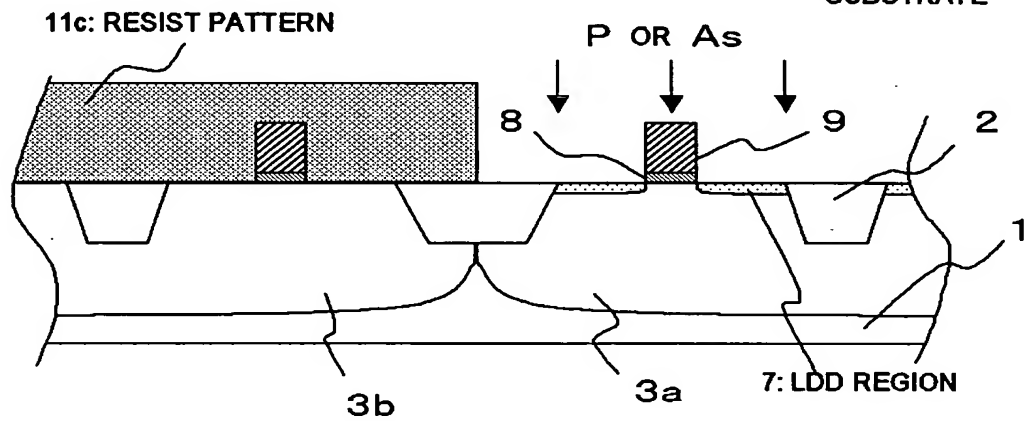


FIG. 3C

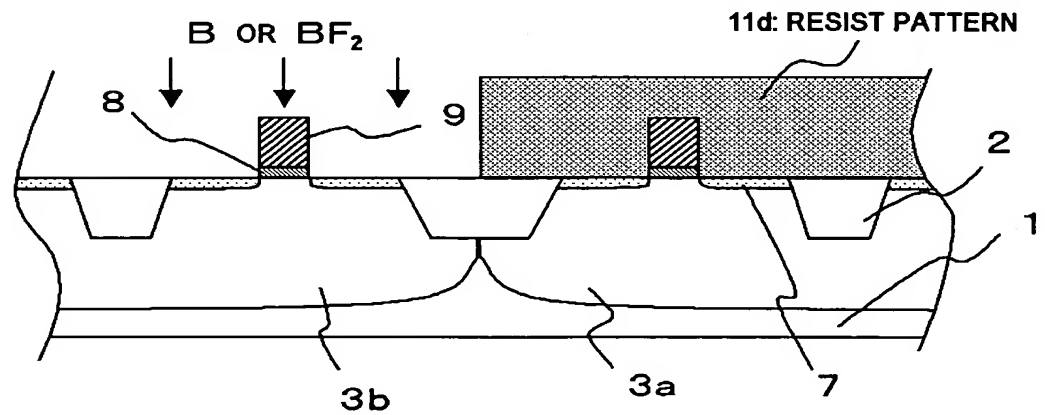
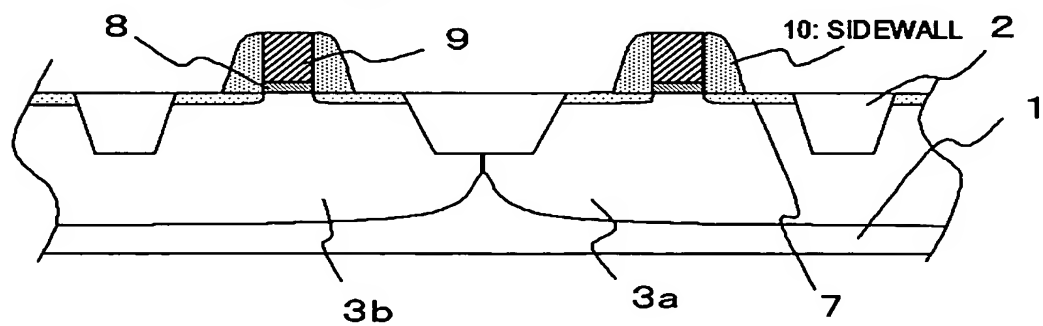


FIG. 3D



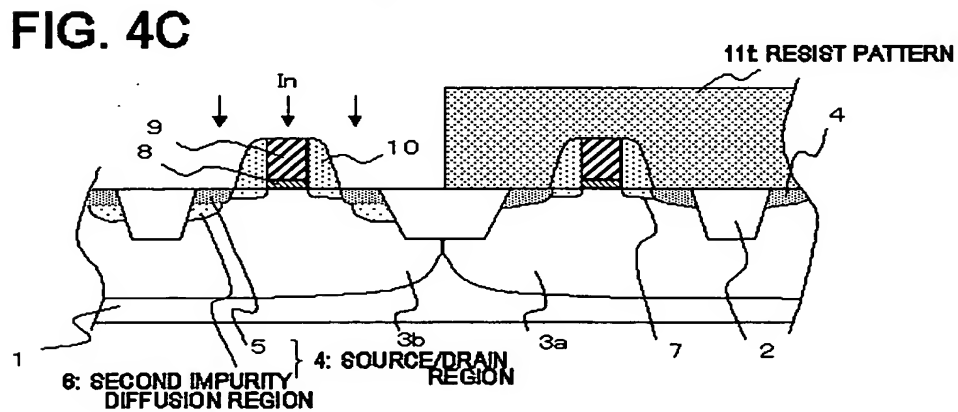
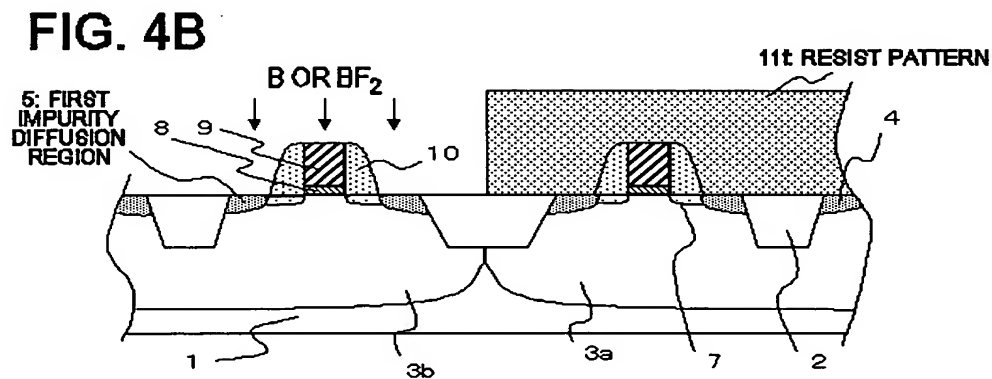
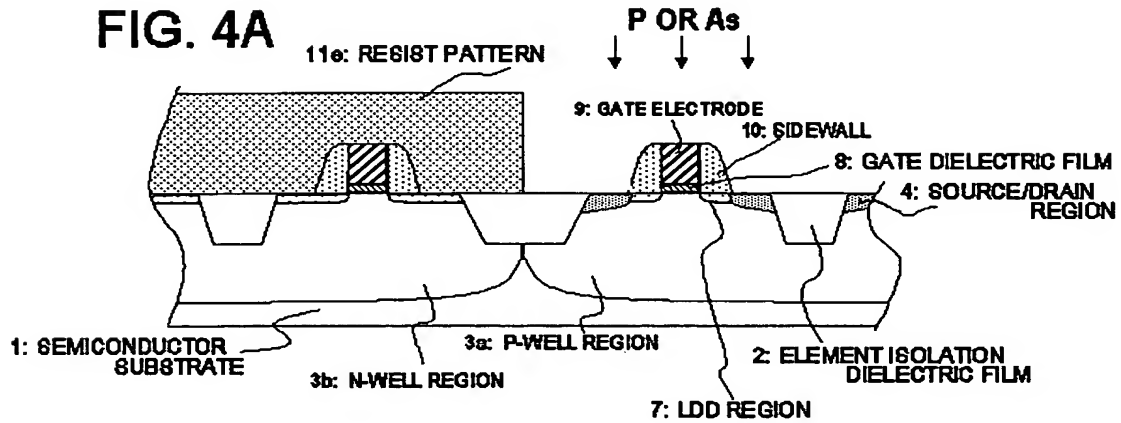


FIG. 5

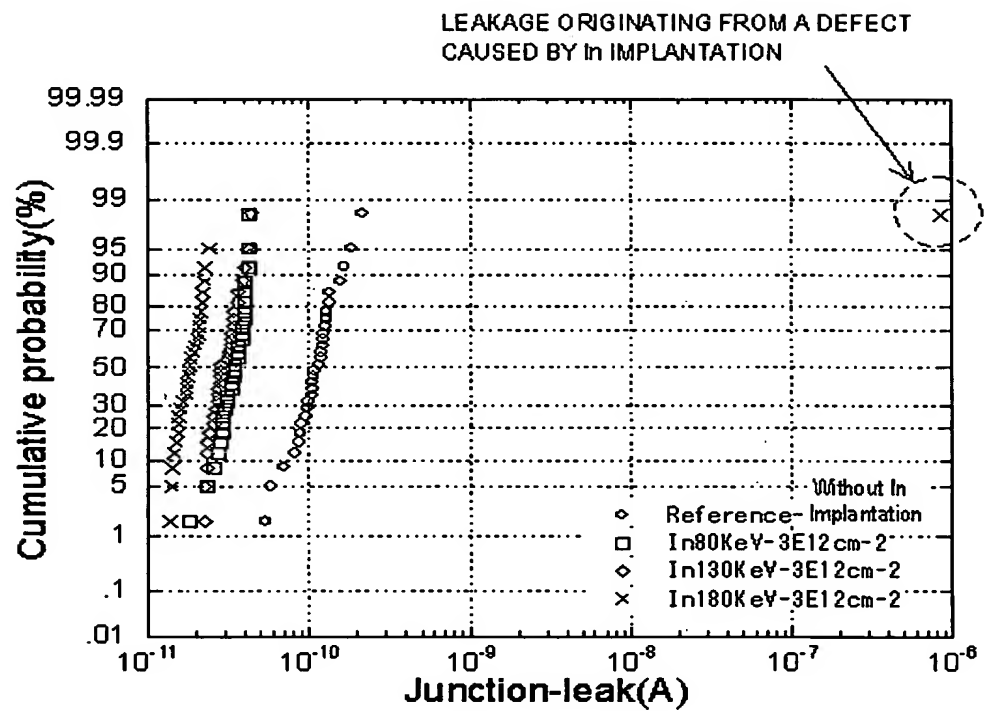


FIG. 6A

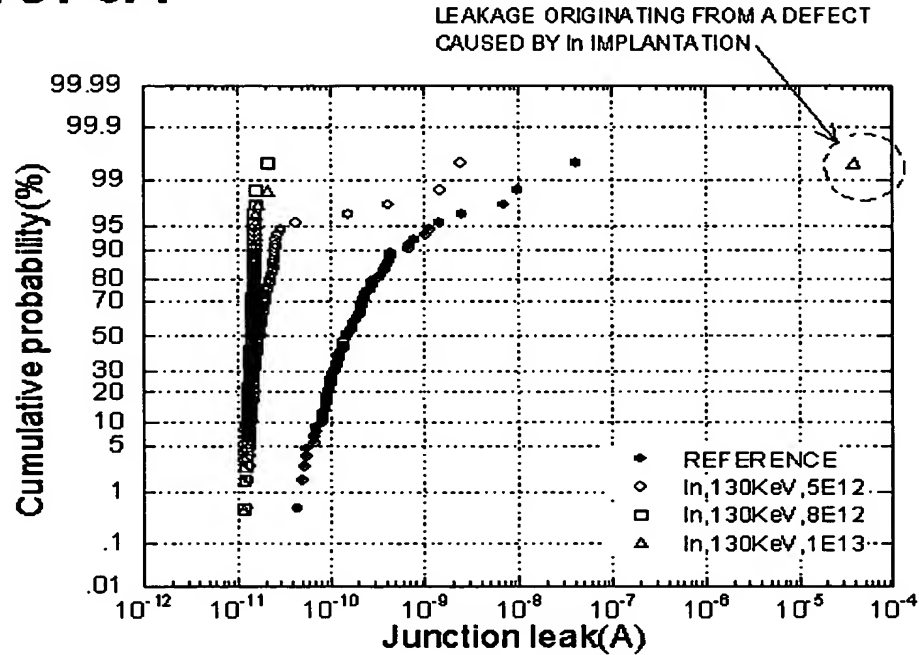


FIG. 6B

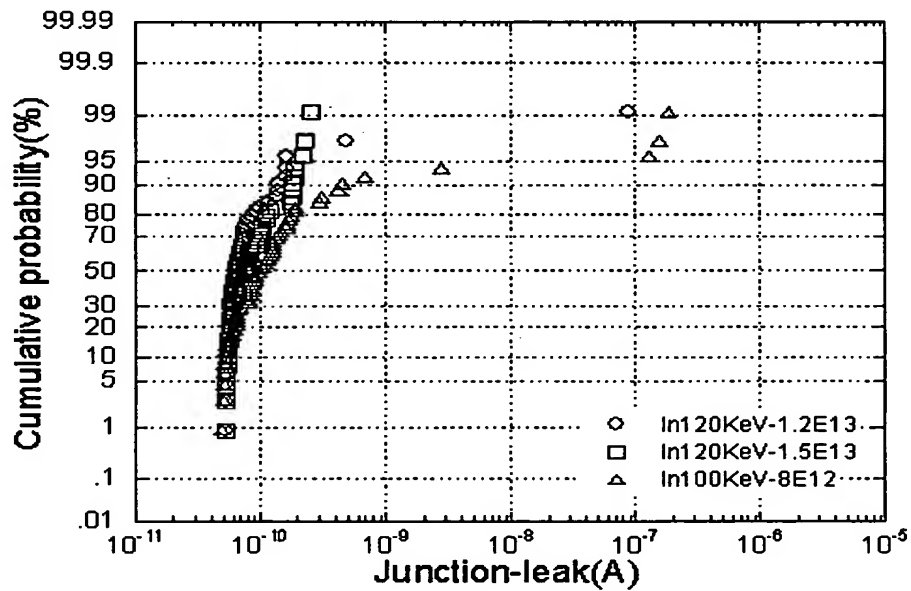


FIG. 7

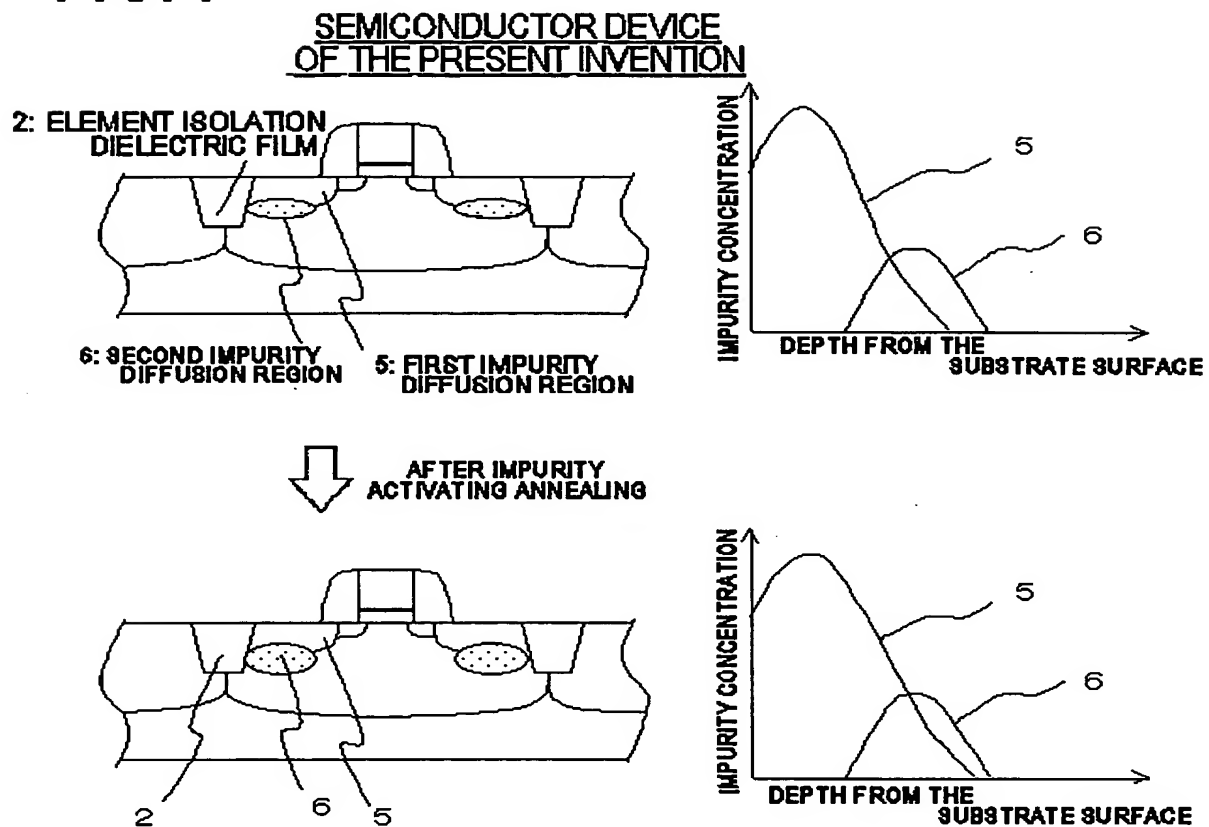


FIG. 8

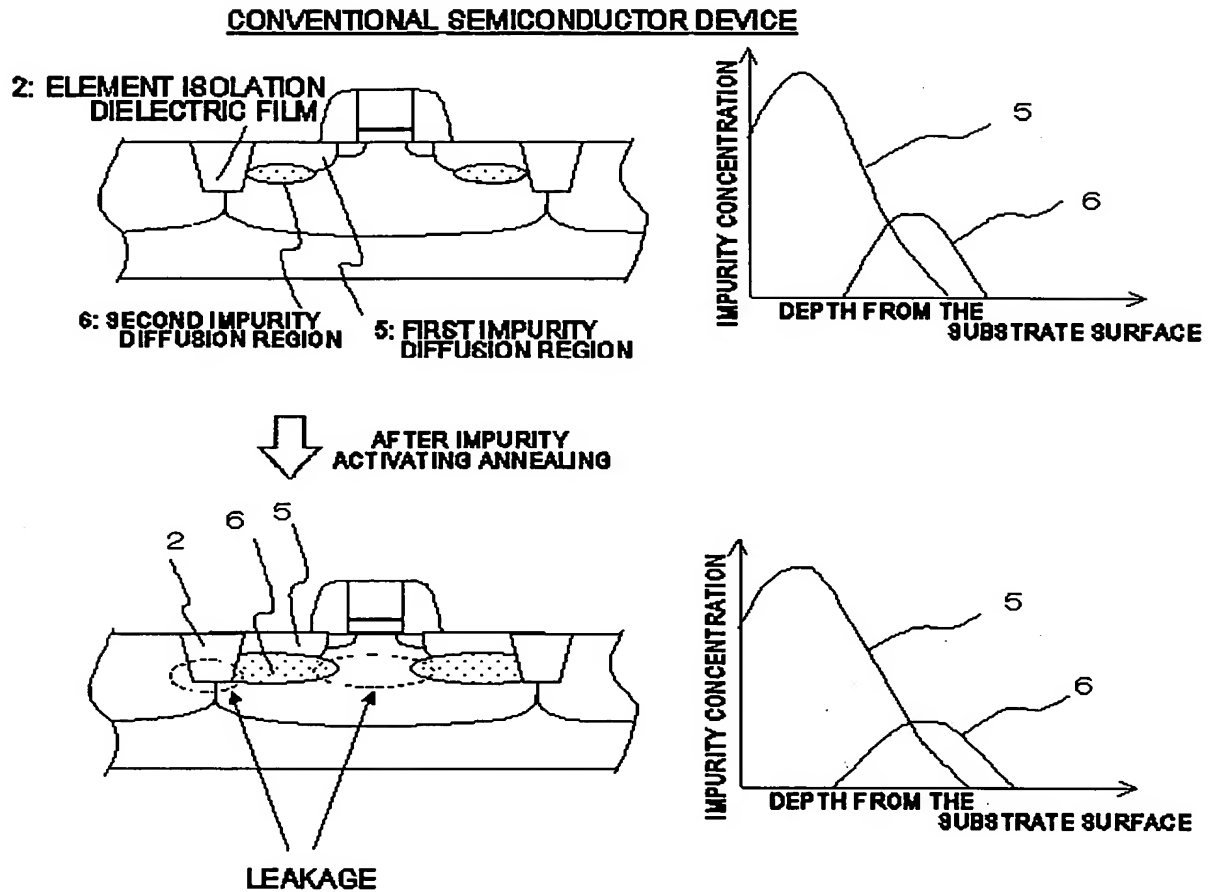


FIG. 9

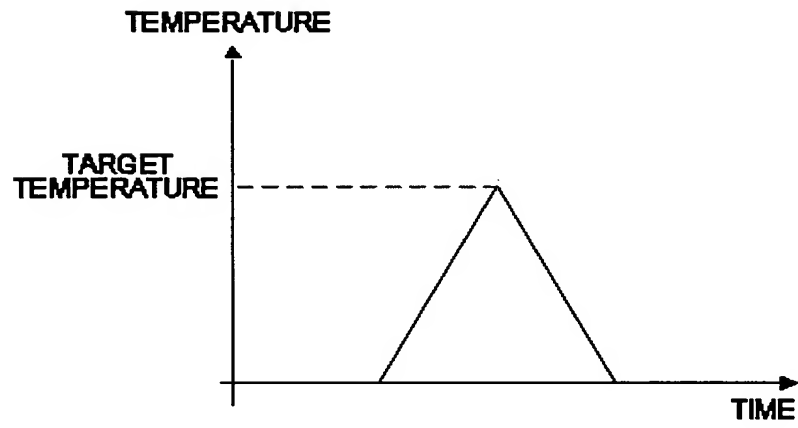


FIG. 10A

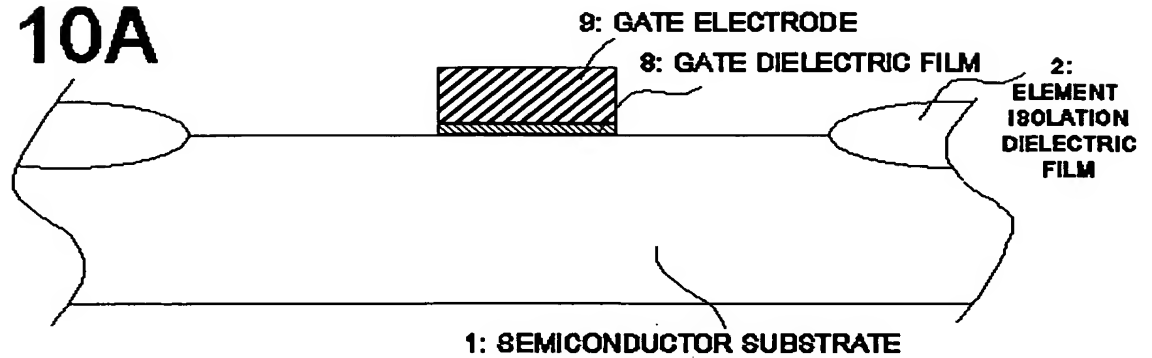


FIG. 10B

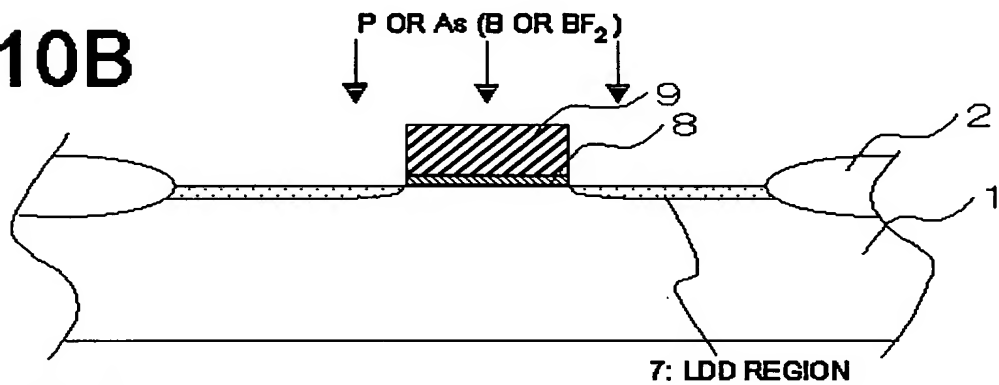


FIG. 10C

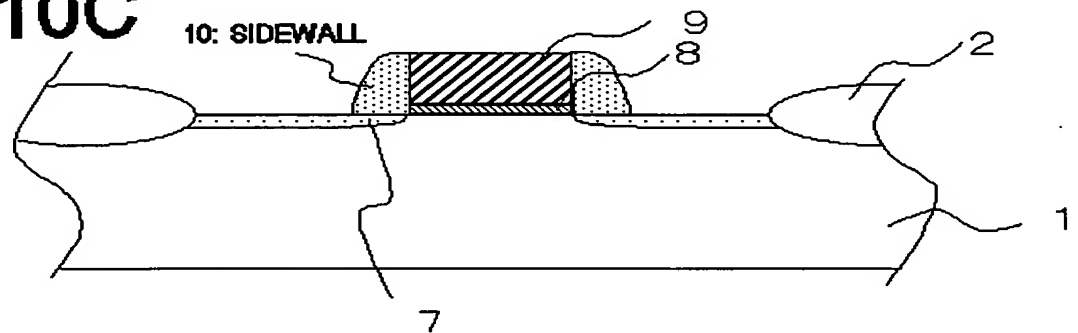


FIG. 10D

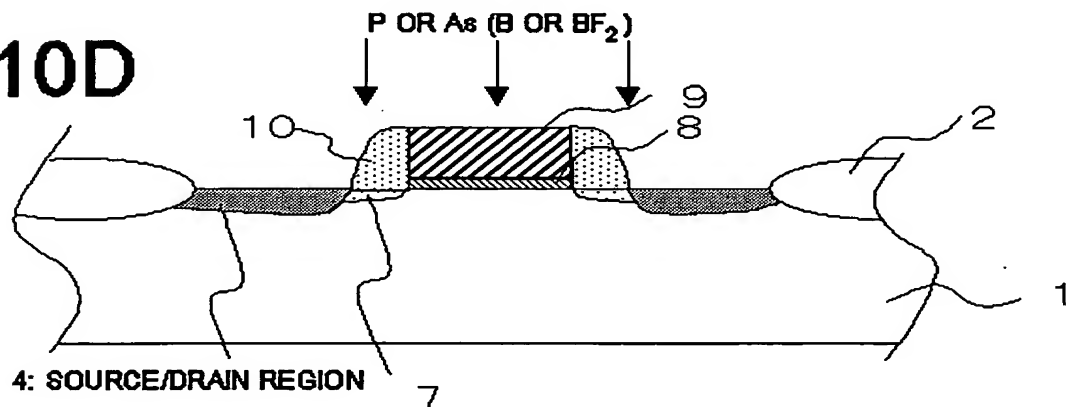


FIG. 11A

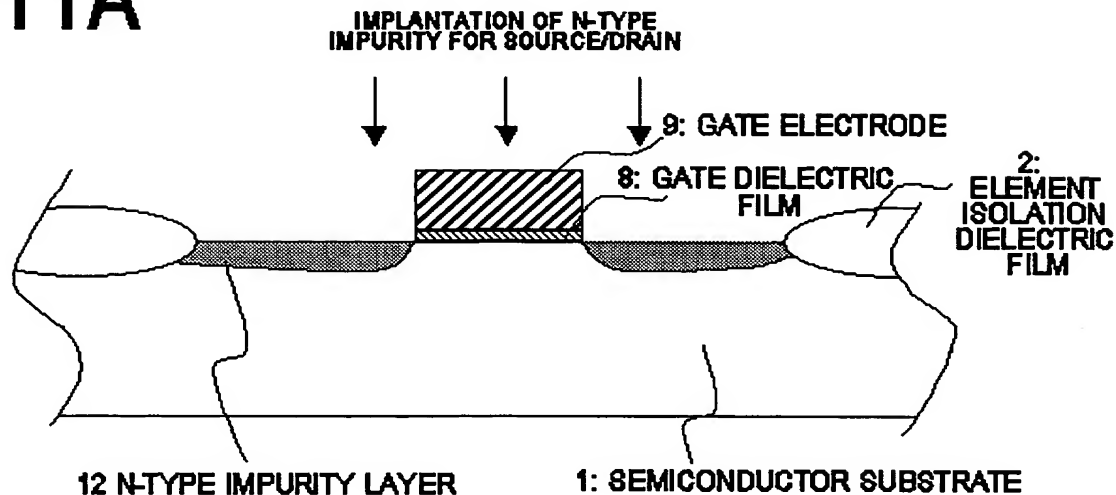


FIG. 11B

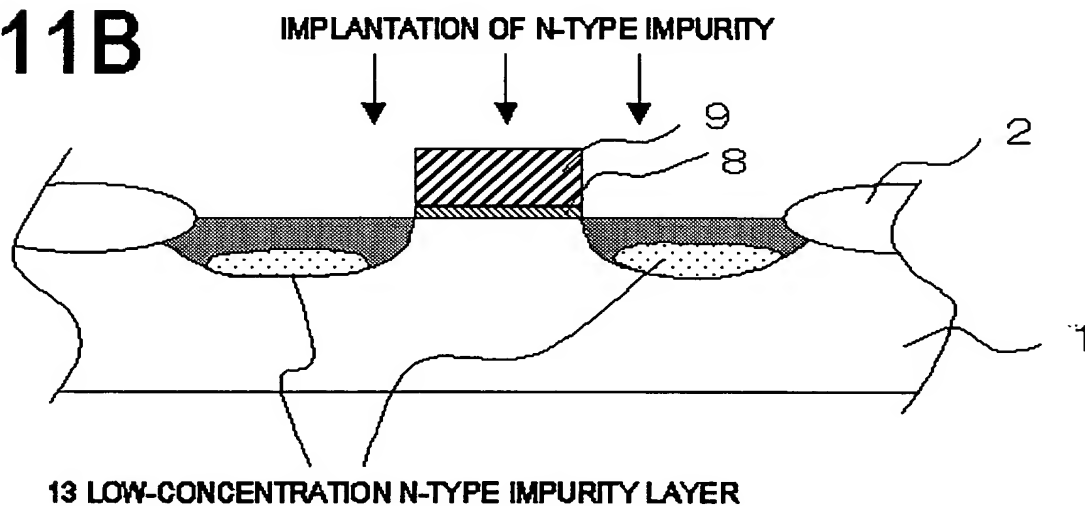


FIG. 11C

